

Abstract

To provide a substrate storage container that enables efficient replacement of the air inside the container main body with a substrate protecting gas. The substrate storage container includes: a container main body 1 capable of accommodating a plurality of semiconductor wafers W; an air feed valve for supplying a purge gas into the container main body 1; and an air replacement unit 40 that blows out the purge gas from the air feed valve into the interior of the container main body 1. The container main body 1 is formed in a front open box form with the air feed valve attached to the rear of the bottom plate 6. The air replacement unit 40 includes a housing 41 for reserving the purge gas from the air feed valve and a cover 52 that covers the open front 42 of the housing 41. The bottom of the housing 41 is connected to the air feed valve so as to flow the purge gas while the housing 41 is supported at the upper portion thereof by a rear wall 18 of the container main body 1. Either the housing 41 or the cover 52 is formed with a plurality of blow holes 55 for blowing the purge gas toward the front 2 of the container main body 1.